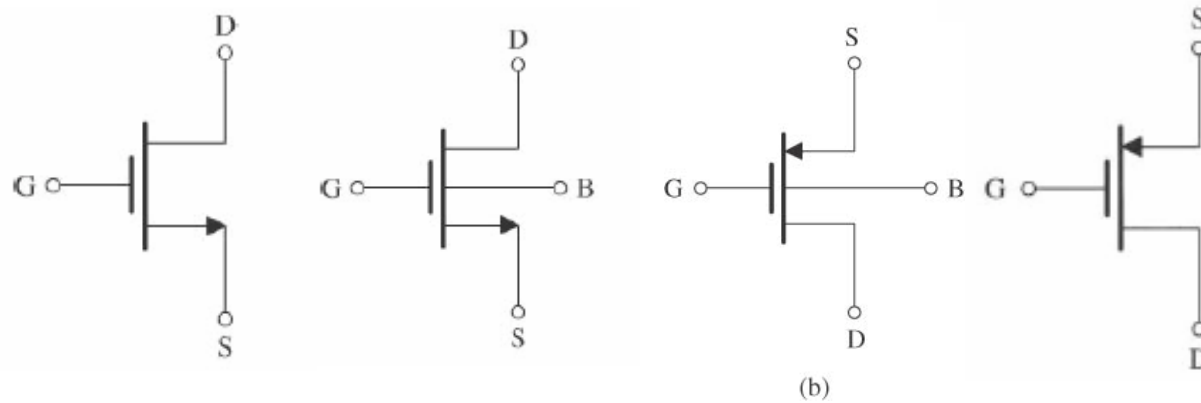
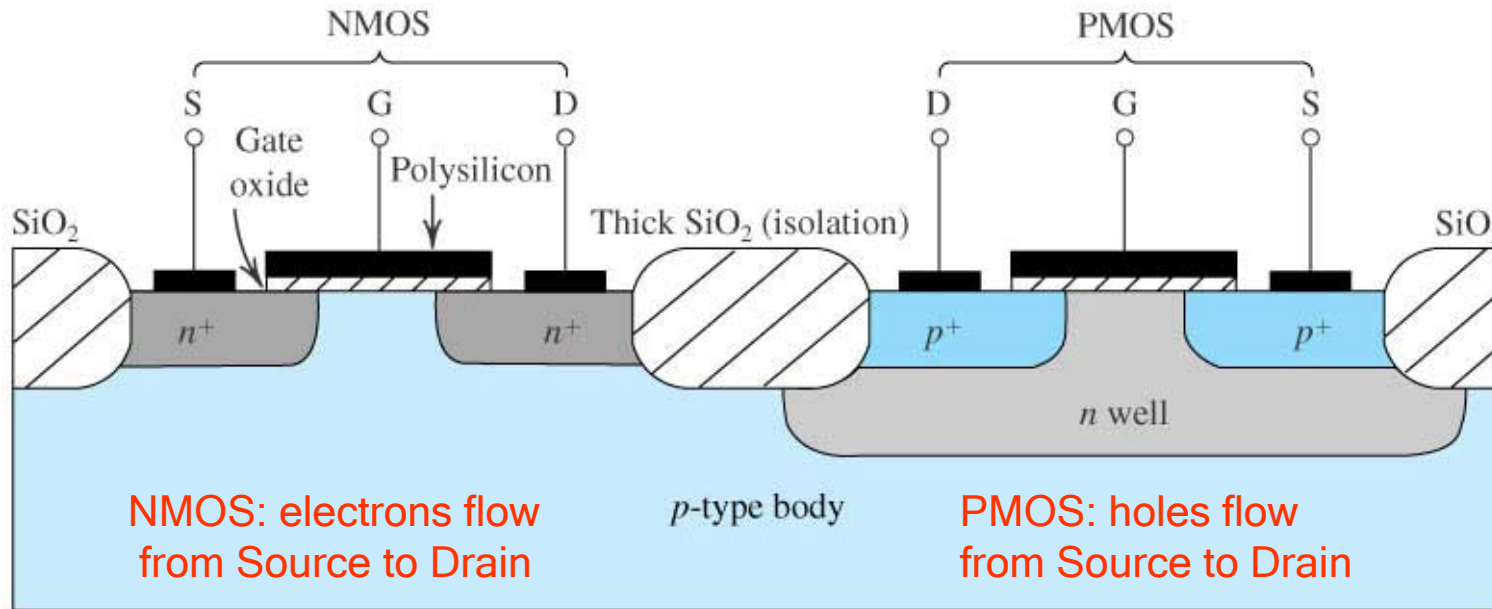
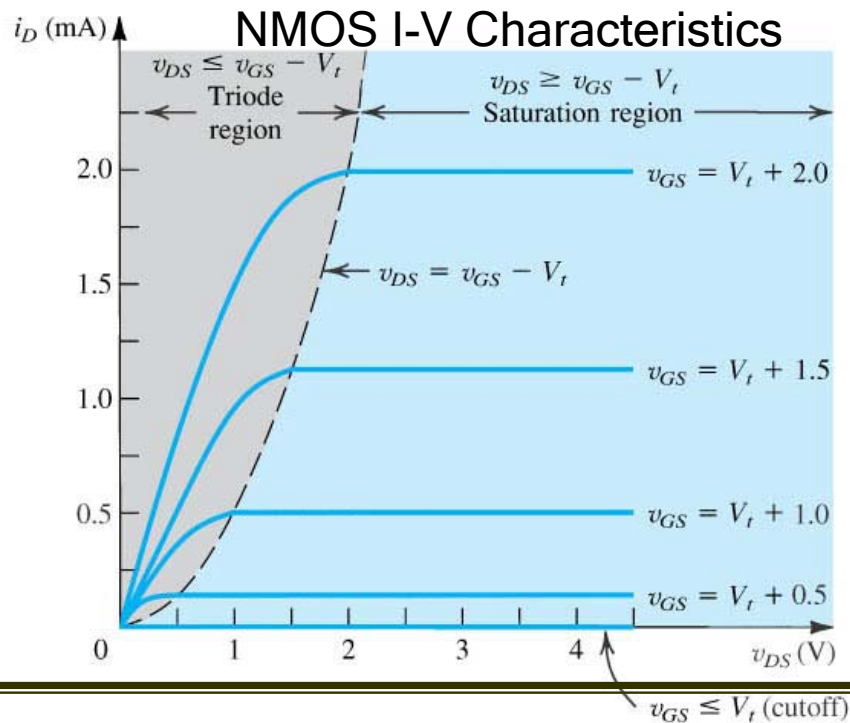
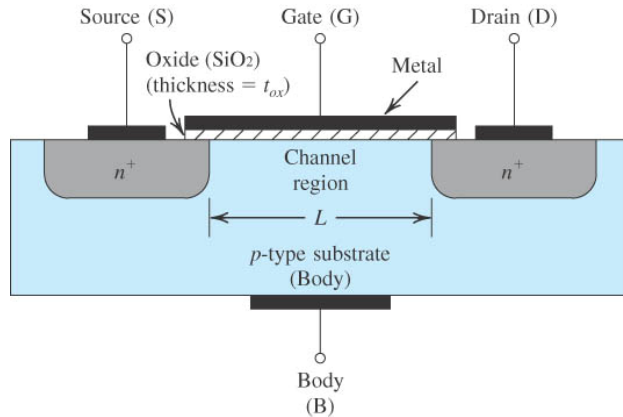


Lect. 3: MOSFET (S&S 4.1 - 4.3)



Lect. 3: MOSFET



(b)

In cut-off ($v_{GS} < V_t$), $i_D = 0$

In triode, ($v_{GS} > V_t$ but $v_{DS} \leq v_{GS} - v_T$)

$$i_D = k' \frac{W}{L} \left[(v_{GS} - V_t) \cdot v_{DS} - \frac{1}{2} v_{DS}^2 \right]$$

In saturation ($v_{GS} > V_t$ and $v_{DS} \geq v_{GS} - v_T$)

$$i_D = \frac{1}{2} k' \frac{W}{L} (v_{GS} - V_t)^2$$

$$k' = \mu_n C_{ox}$$

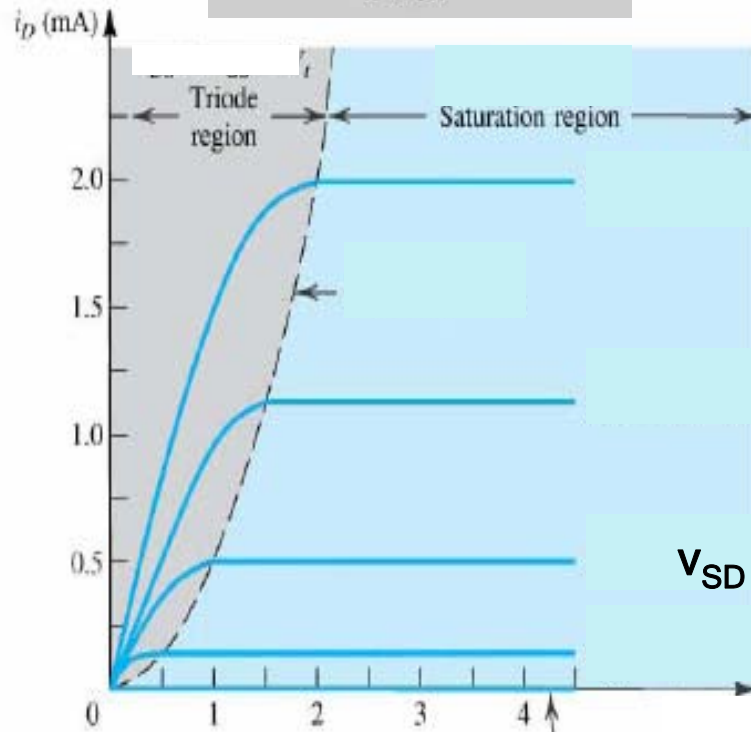
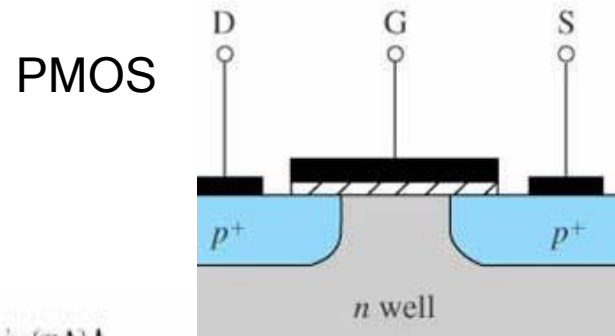
μ_n : electron mobility

C_{ox} : oxide capacitance

V_t : threshold voltage



Lect. 3: MOSFET



$$v_{SG} < |V_t| : i_D = 0$$

$$v_{SG} > |V_t| \text{ and } v_{SD} < v_{SG} - |V_t| \text{ (triode):}$$

$$i_D = \mu_p C_{ox} \frac{W}{L} \left[(v_{SG} - |V_t|) \cdot v_{SD} - \frac{1}{2} v_{SD}^2 \right]$$

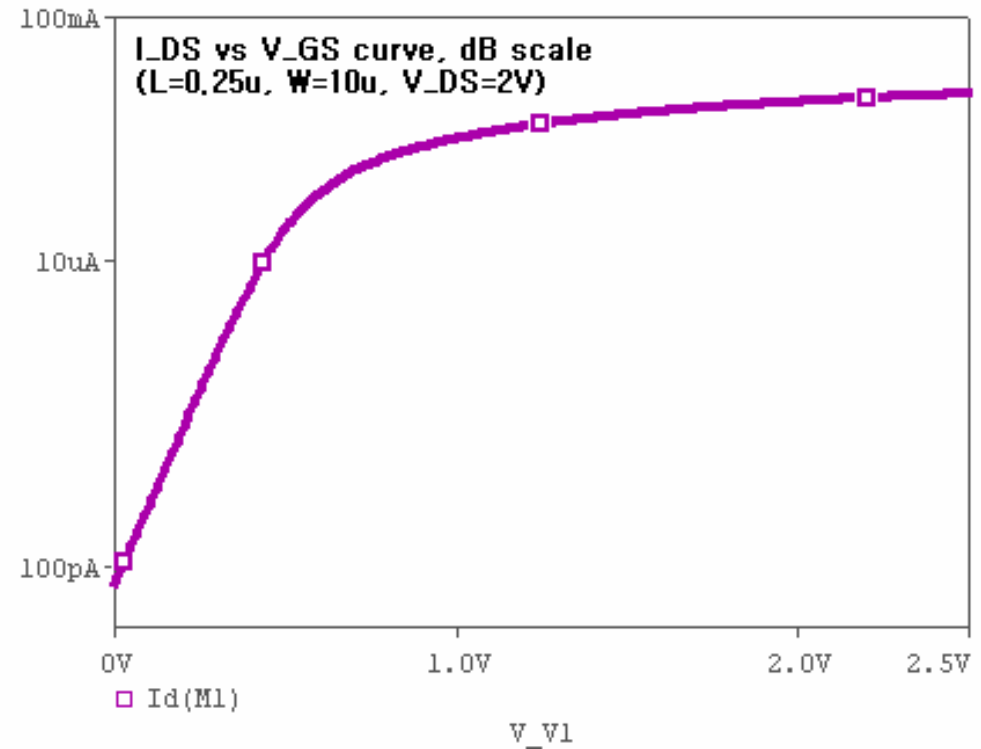
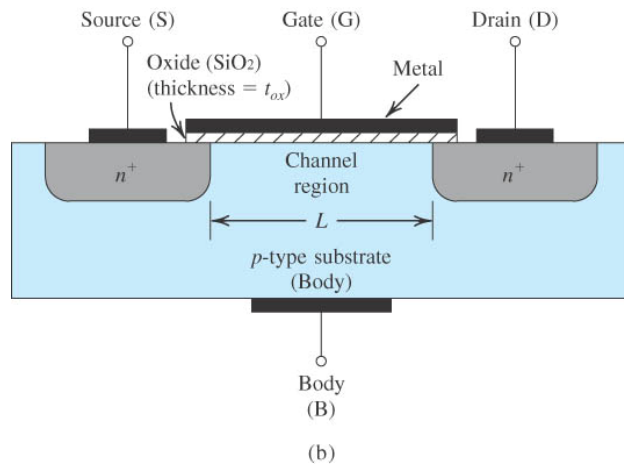
$$v_{SG} > |V_t| \text{ and } v_{SD} > v_{SG} - |V_t| \text{ (saturation):}$$

$$i_D = \frac{1}{2} \mu_p C_{ox} \frac{W}{L} (v_{SG} - |V_t|)^2$$

Lect. 3: MOSFET

Deviation from the ideal model

1) $I_D = 0$ in Cut-Off ?

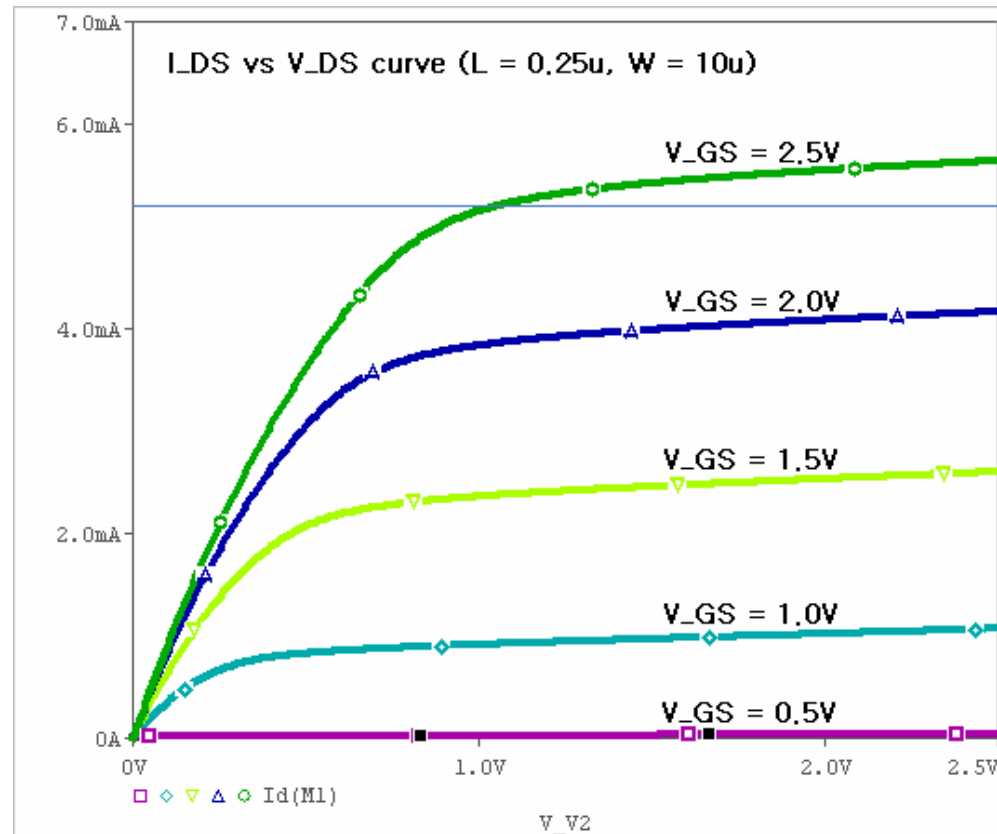


Leakage through the oxide: more significant for thinner oxide (smaller MOSFET)

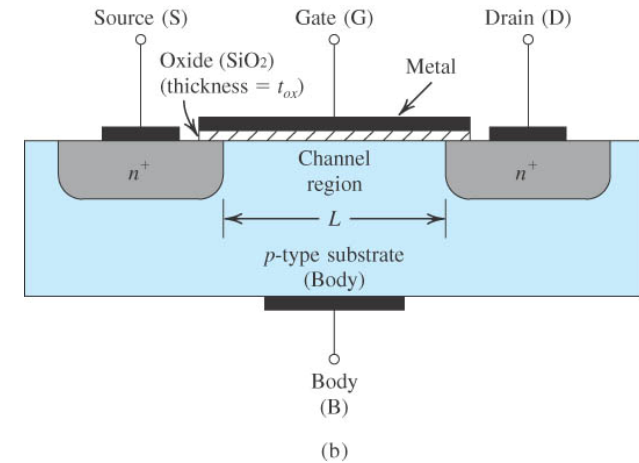
→ Significant problem in modern digital circuits

Lect. 3: MOSFET

2) In saturation,
$$i_D = \frac{1}{2} k' \frac{W}{L} (v_{GS} - V_t)^2$$



But I_D increases with v_{DS} even in saturation



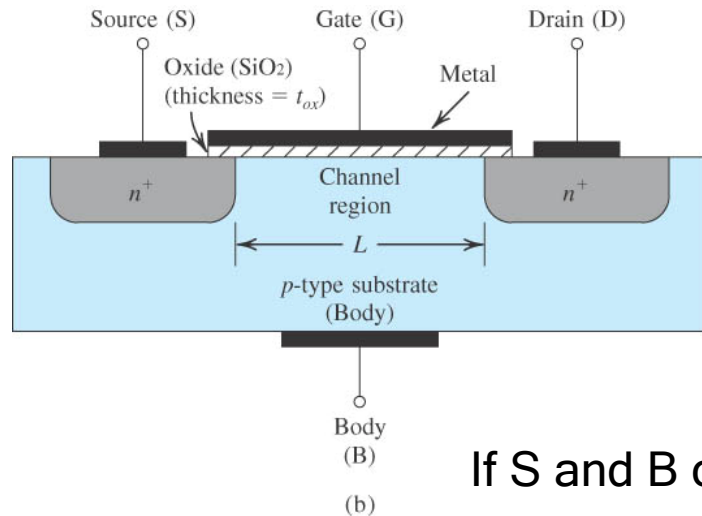
v_{DS} increase causes reduction in actual channel length.

→ Channel length modulation.

$$i_D = \frac{1}{2} k' \frac{W}{L} (1 + \lambda \cdot v_{DS}) (v_{GS} - V_t)^2$$

Lect. 3: MOSFET

3) Body effect: Voltage applied to B causes a change in threshold voltage



$$V_t = V_{t0} + \gamma [\sqrt{2\phi_f + V_{SB}} - \sqrt{2\phi_f}]$$

$$V_t = V_{t0} \text{ when } V_{SB} = 0$$

ϕ_f and γ process-dependent parameters

If S and B can be tied, no body effect.

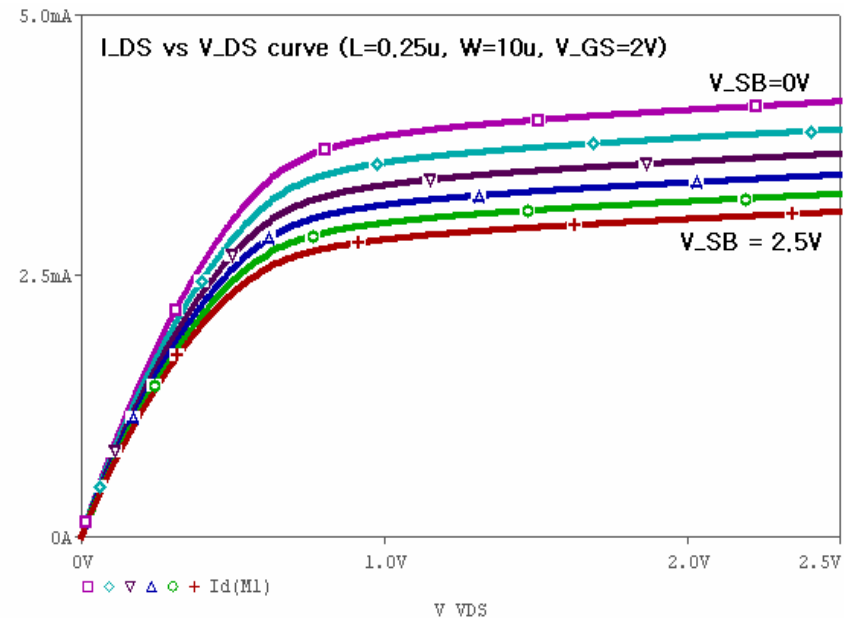
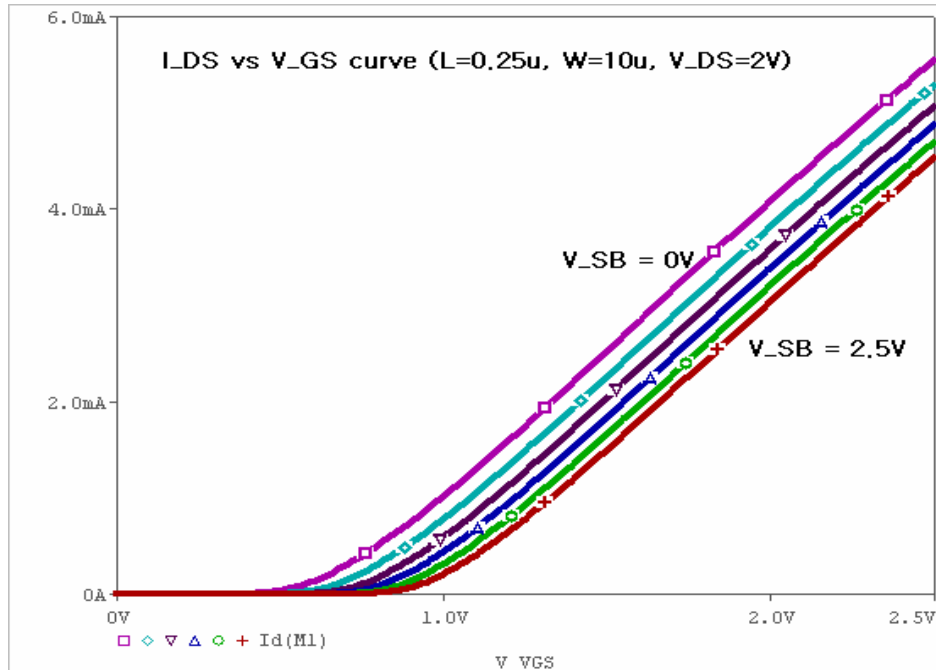
In IC, B is connected to

- the most negative supply voltage (NMOS)
- the most positive supply voltage (PMOS)

→ V_t depends on V_S

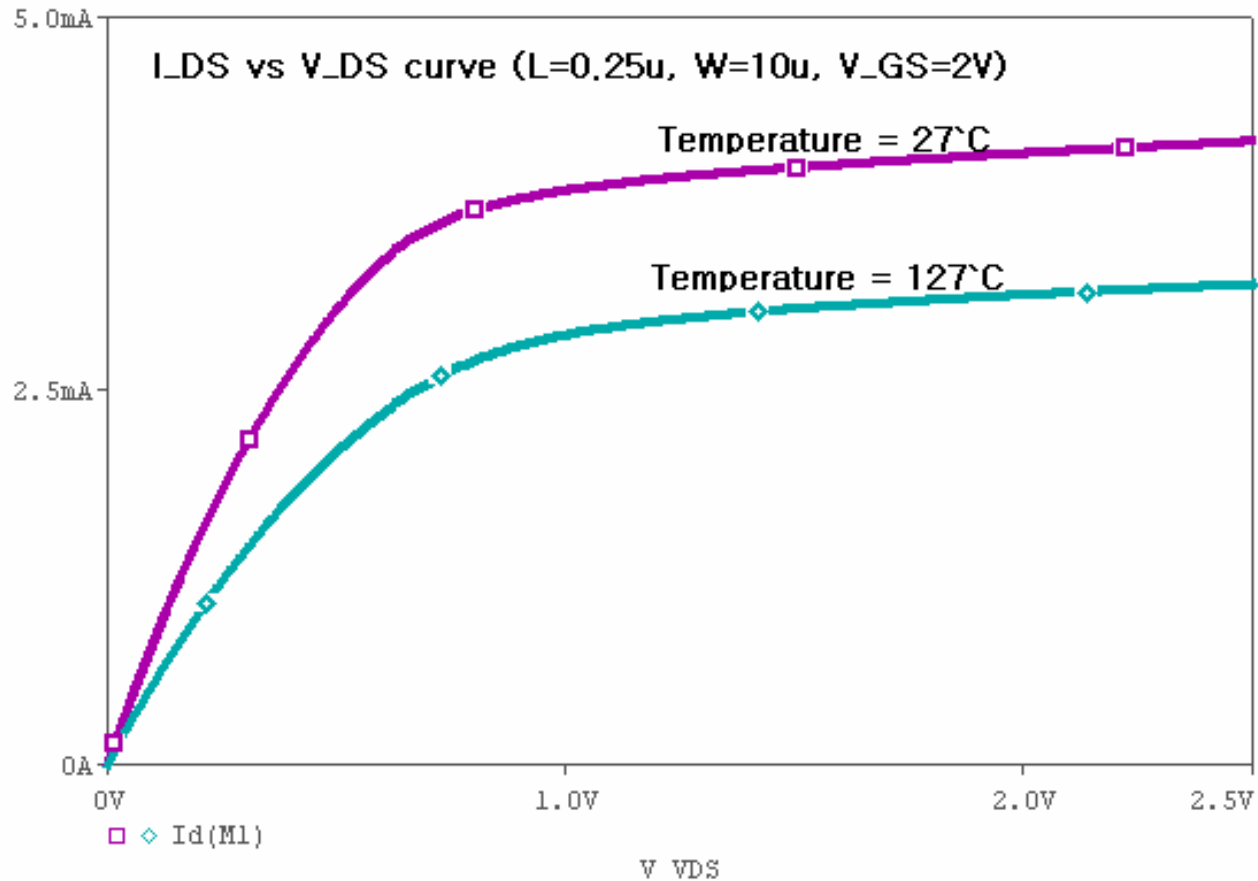
Lect. 3: MOSFET

Body effect: Voltage applied to B causes a change in threshold voltage.



Lect. 3: MOSFET

4) Temperature effect: Many MOSFET parameters are temperature dependent



Higher temperature causes reduction in I_D

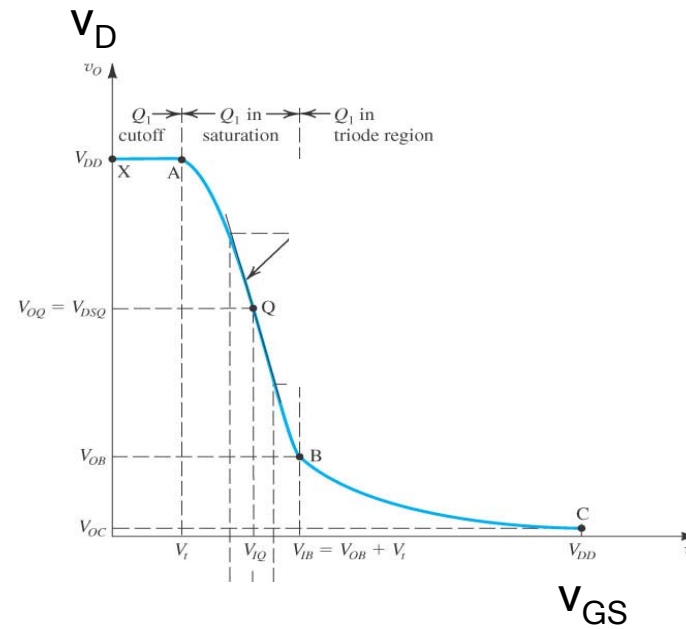
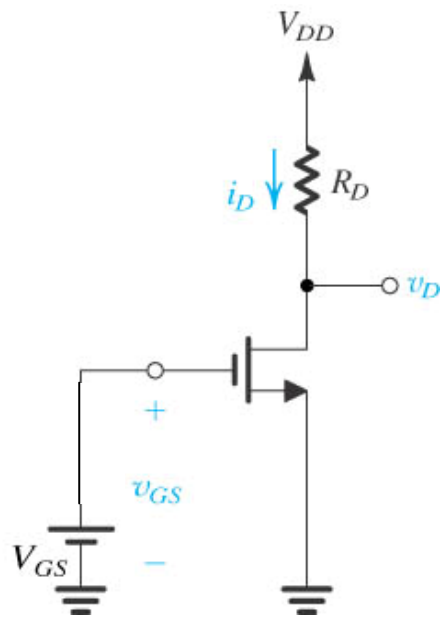
Lect. 3: MOSFET

- Modern transistors are very complicated in their structure.
- Many parameters are needed to model their characteristics accurately in SPICE
- SPICE parameters for 0.25 μ m NMOS are shown
- For detailed explanations, See *MOSFET Users' Manual* at www-device.eecs.berkeley.edu/~bsim3/get.html
- Although complicated, they can precisely model the transistor characteristics and accurate circuit design is possible

```
MODEL orbit2L2N NMOS ( LEVEL = 7
+TNOM = 27 TOX = 5.6E-9
+XJ = 1E-7 NCH = 2.3549E17 VTH0 = 0.3654765
+K1 = 0.4732214 K2 = 7.994532E-4 K3 = 1E-3
+K3B = 3.0713494 W0 = 1E-7 NLX = 1.617898E-7
+DVT0W = 0 DVT1W = 0 DVT2W = 0
+DVT0 = 0.455178 DVT1 = 0.6258687 DVT2 = -0.5
+U0 = 280.4589023 UA = -1.607126E-9 UB = 2.806549E-18
+UC = 3.290051E-11 VSAT = 1.07496E5 A0 = 1.8770435
+AGS = 0.3310181 B0 = -3.173524E-8 B1 = -1E-7
+KETA = -8.69841E-3 A1 = 8.317145E-5 A2 = 0.6592347
+RDSW = 200 PRWG = 0.4477477 PRWB = 0.0208175
+WR = 1 WINT = 0 LINT = 1.392558E-10
+DWG = -2.28419E-8
+DWB = -6.95781E-10 VOFF = -0.0910963 NFACTOR = 1.202941
+CIT = 0 CDSC = 2.4E-4 CDSCD = 0
+CDSCB = 0 ETA0 = 5.0732E-3 ETAB = 6.262008E-5
+DSUB = 0.0310034 PCLM = 1.5101091 PDIBLC1 = 0.897659
+PDIBLC2 = 2.924029E-3 PDIBLCB = 0.0651312 DROUT = 1
+PSCBE1 = 7.017738E8 PSCBE2 = 2.271109E-4 PVAG = 8.531511E-3
+DELTA = 0.01 RSH = 4.6 MOBMOD = 1
+PRT = 0 UTE = -1.5 KT1 = -0.11
+KT1L = 0 KT2 = 0.022 UA1 = 4.31E-9
+UB1 = -7.61E-18 UC1 = -5.6E-11 AT = 3.3E4
+WL = 0 WLN = 1 WW = 0
+WWN = 1 WWL = 0 LL = 0
+LLN = 1 LW = 0 LWN = 1
+LWL = 0 CAPMOD = 2 XPART = 0.5
+CGDO = 4.59E-10 CGSO = 4.59E-10 CGBO = 5E-10
+CJ = 1.78338E-3 PB = 0.99 MJ = 0.4661295
+CJSW = 4.154041E-10 PBSW = 0.9563049 MJSW = 0.3162462
+CF = 0 PVTH0 = -9.648921E-3 PRDSW = -10
+PK2 = 3.534961E-3 WKETA = 0.0120981 LKETA = -3.31688E-3 )
```

Lect. 3: MOSFET

Linearization of MOSFET: → Small-signal circuit



(c)

Lect. 3: MOSFET

Small signal model for NMOS

$$v_{GS} = V_{GS} + v_{gs}, \quad v_{DS} = V_{DS} + v_{ds}$$

$$i_G = I_G + i_g, \quad i_D = I_D + i_d$$

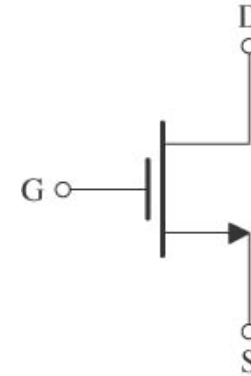
→ i_g, i_d as functions of v_{gs}, v_{ds}

$$i_g = 0$$

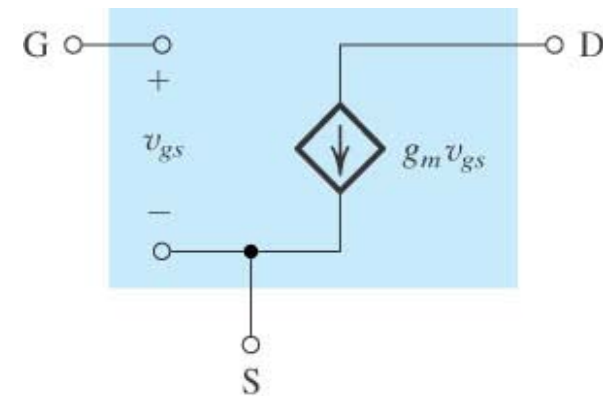
$$\text{From } i_D = \frac{1}{2} \mu_n C_{ox} \frac{W}{L} (v_{GS} - V_T)^2 \text{ with } v_{GS} = V_{GS} + v_{gs}$$

$$i_d \approx \left[\frac{1}{2} \mu_n C_{ox} \frac{W}{L} (V_{GS} - V_T) \right]^2 + \frac{di_D}{dv_{GS}} \Big|_{V_{GS}} \cdot v_{gs}$$

$$\therefore i_d = \mu_n C_{ox} \frac{W}{L} (V_{GS} - V_T) \cdot v_{gs} = g_m \cdot v_{gs}$$



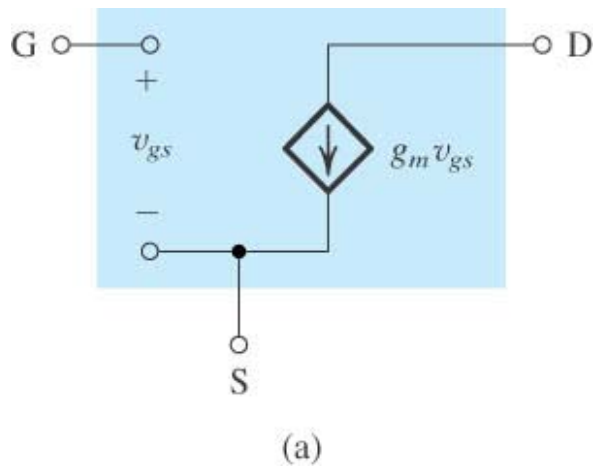
(c)



(a)

Lect. 3: MOSFET

Various expressions for g_m



$$\text{From } i_D = \frac{1}{2} \mu_n C_{ox} \frac{W}{L} (v_{GS} - V_T)^2$$

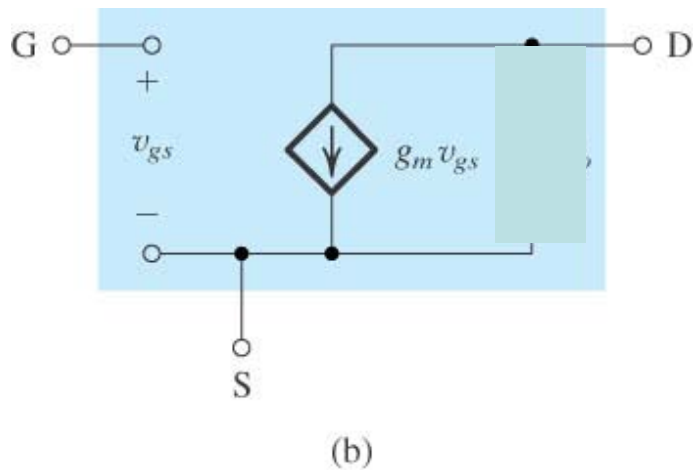
$$g_m = \left. \frac{di_D}{dv_{GS}} \right|_{V_{GS}} = \mu_n C_{ox} \frac{W}{L} (V_{GS} - V_T)$$

$$= \frac{2I_D}{V_{GS} - V_T}$$

$$= \sqrt{2\mu_n C_{ox} \cdot \frac{W}{L} \cdot I_D}$$

Lect. 3: MOSFET

Small-signal model including channel-length modulation



$$i_D = \frac{1}{2} k' \frac{W}{L} (1 + \lambda \cdot v_{DS}) (v_{GS} - V_t)^2$$

$$\Delta i_D = \frac{\partial i_D}{\partial v_{GS}} \cdot \Delta v_{GS} + \frac{\partial i_D}{\partial v_{DS}} \cdot \Delta v_{DS}$$

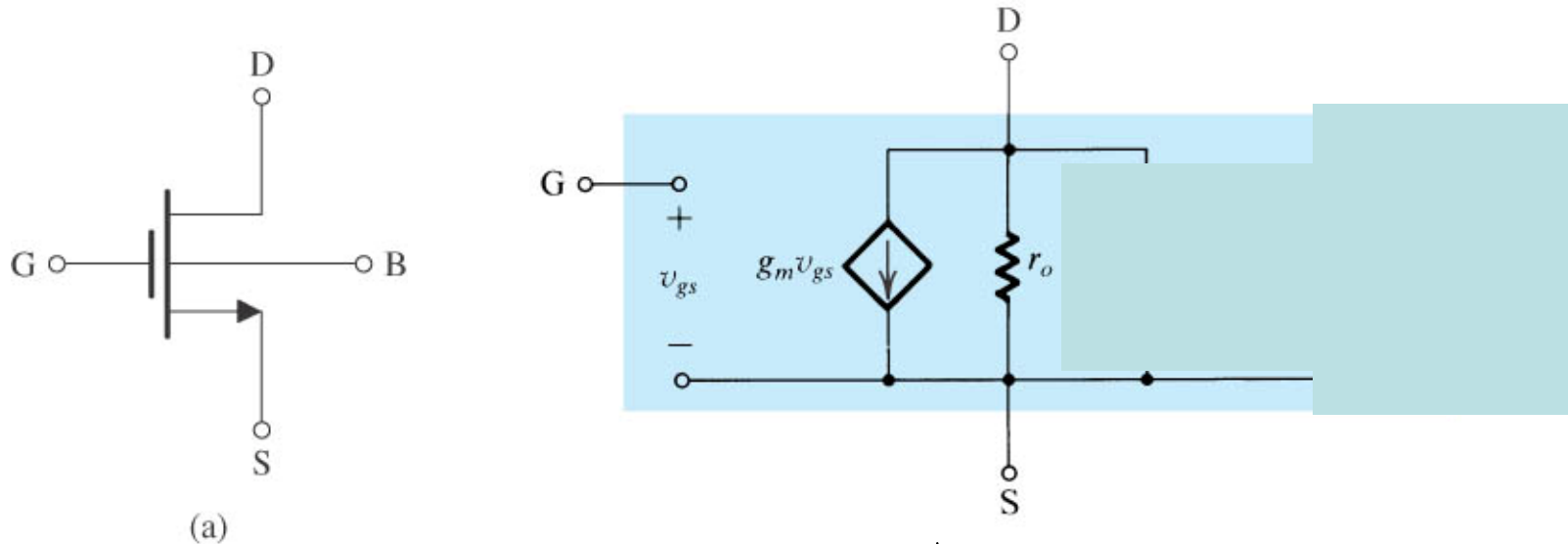
$$\frac{\partial i_D}{\partial v_{GS}} = g_m$$

$$\frac{\partial i_D}{\partial v_{DS}} = \frac{1}{2} k' \frac{W}{L} \lambda (v_{GS} - V_t)^2 = \frac{1}{r_0} \quad \text{Often, } r_0 = \frac{V_A}{I_D}$$

$$i_d = g_m \cdot v_{gs} + \frac{v_{ds}}{r_0}$$

Lect. 3: MOSFET

Small-signal model including Body effect



Practically, Body Effect
Is not easy to model analytically.

→ Simulation

$$g_{mb} \equiv \left. \frac{\partial i_D}{\partial v_{BS}} \right|_{\substack{v_{GS} = \text{constant} \\ v_{DS} = \text{constant}}}$$

$$g_{mb} \equiv \chi g_m \quad (\chi : 0.1 - 0.3)$$